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Applicant

Raghuram Narayan

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Group Art Unit

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## INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)		
TN	C01	Timothy Day, Frank Luecke, Michael Brownell, <i>Continuously Tunable Diode Lasers</i> , New Focus, Inc., Mountain View, California, Lasers & Optonics, June 1993, 6 pages
	C02	F.J. Duarte, <i>Multiple-prism granting designs tune diode lasers</i> , Laser Focus World, February 1993, pp. 103-109
	C03	M. de Lebachellerie, G. Passedat, <i>Mode-hop suppression of Littrow granting-tuned lasers</i> , Applied Optics Vol. 32, No. 3, January 20, 1993, pp. 269-274
	C04	Michael G. Littman, <i>Single-Mode Operation of Grazing-Incidence Pulsed Dye Laser</i> , Optical Society of America, Optics Letters, Vol. 3, No. 4, October 1978, pp.138-140
	C05	<i>82 nm of Continuous Tunability for an External Cavity Semiconductor Laser</i> , Electronics Letters, Vol. 27, No. 2, January 17, 1991, pp.183-184
	C06	Dr. Timothy Day, <i>External Cavity Tunable Lasers for Network Deployments</i> , New Focus, Inc., San Jose, California, IEEE 2001 0-7803-7100-3/01, March 2001, pp.39-40
	C07	Haim Lotem, <i>Littrow-Mounted Diffraction Granting Cavity</i> , Applied Optics, Vol. 33, No. 6, February 20, 1994, pp.930-934
	C08	Paul Zorabedian, <i>Characteristics of a Granting-External-Cavity Semiconductor Laser Containing Intracavity Prism Beam Expanders</i> , Jurnal of Lightware Technology, Vol. 10, No. 3, March 1992, pp.330-335
	C09	W.R. Trutna, L.F. Strokes, <i>Continuously Tuned External Cavity Semiconductor Laser</i> , Jurnal of Lightware Technology, Vol. 11, No. 8, August 1993, pp. 1279-1286

EXAMINER

DATE CONSIDERED

9/21/05

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.